

=> d his

(FILE 'HOME' ENTERED AT 09:42:26 ON 21 JAN 2004)

FILE 'REGISTRY' ENTERED AT 09:43:03 ON 21 JAN 2004

L1 STRUCTURE UPLOADED  
L2 QUE L1  
L3 6 S L1 SSS SAM  
L4 6 S L2 SSS SAM

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 09:44:18 ON 21 JAN 2004

L5 13 S L4  
L6 6 DUPLICATE REMOVE L5 (7 DUPLICATES REMOVED)

FILE 'HOME' ENTERED AT 09:45:09 ON 21 JAN 2004

FILE 'REGISTRY' ENTERED AT 09:48:02 ON 21 JAN 2004

L7 SCREEN 2067  
L8 STRUCTURE UPLOADED  
L9 QUE L8 AND L7  
L10 0 S L9 SSS SAM

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 09:48:42 ON 21 JAN 2004

L11 0 S L10

FILE 'HOME' ENTERED AT 09:48:58 ON 21 JAN 2004

FILE 'REGISTRY' ENTERED AT 09:49:27 ON 21 JAN 2004

L12 SCREEN 2067  
L13 STRUCTURE UPLOADED  
L14 QUE L13 AND L12  
L15 0 S L14 SSS SAM

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 09:51:32 ON 21 JAN 2004

L16 0 S L15

FILE 'HOME' ENTERED AT 09:51:43 ON 21 JAN 2004

FILE 'REGISTRY' ENTERED AT 09:54:29 ON 21 JAN 2004

L17 SCREEN 2067  
L18 STRUCTURE UPLOADED  
L19 QUE L18 AND L17  
L20 0 S L19 SSS SAM  
L21 SCREEN 2067  
L22 STRUCTURE UPLOADED  
L23 QUE L22 AND L21  
L24 2 S L23 SSS SAM  
L25 SCREEN 2067  
L26 STRUCTURE UPLOADED  
L27 QUE L26 AND L25  
L28 0 S L27 SSS SAM  
L29 SCREEN 2067  
L30 STRUCTURE UPLOADED  
L31 QUE L30 AND L29  
L32 1 S L31 SSS SAM

=> FIL HCAPLUS, CAPLUS, USPATFULL  
COST IN U.S. DOLLARS

SINCE FILE  
ENTRY  
3.36

TOTAL  
SESSION  
42.40

FULL ESTIMATED COST

FILE 'HCAPLUS' ENTERED AT 09:59:08 ON 21 JAN 2004

USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.  
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.

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FILE 'CAPLUS' ENTERED AT 09:59:08 ON 21 JAN 2004

USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.  
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.

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FILE 'USPATFULL' ENTERED AT 09:59:08 ON 21 JAN 2004

CA INDEXING COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

=> s l20

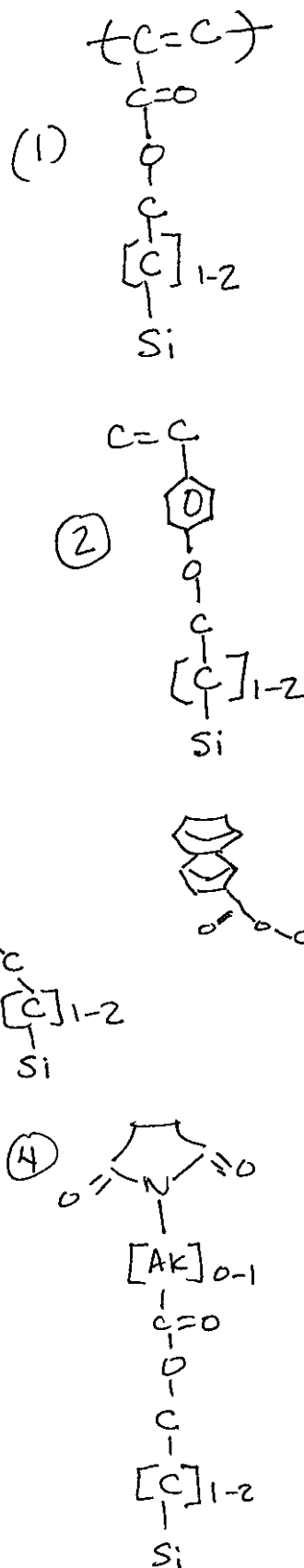
L33 0 L20

=> s l24

L34 11 L24

=> s l28

L35 0 L28



=> s 132

L36 2 L32

=> s 134 or 136

L37 13 L34 OR L36

=> duplicates remove 137

DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS, USPATFULL'

KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n

PROCESSING COMPLETED FOR L37

L38 7 DUPLICATE REMOVE L37 (6 DUPLICATES REMOVED)

=> d 138 1-7 ibib hitstr

L38 ANSWER 1 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 1

ACCESSION NUMBER: 2003:216878 HCAPLUS

DOCUMENT NUMBER: 138:242881

TITLE: Skin cosmetic compositions containing active ingredients and specified polysiloxanes

INVENTOR(S): Hayashi, Kyoko; Mitamura, Joji; Tokunaga, Yoshihiro

PATENT ASSIGNEE(S): Lion Corp., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 26 pp.

CODEN: JKXXAF

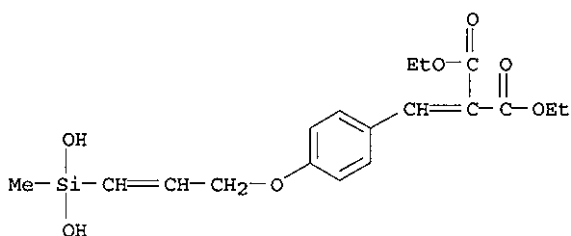
DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003081806	A2	20030319	JP 2001-270198	20010906
PRIORITY APPLN. INFO.: JP 2001-270198 20010906				
IT 501947-86-0D, trimethyl-silyl-terminated				
RL: COS (Cosmetic use); BIOL (Biological study); USES (Uses)				
(assumed monomers; skin cosmetic compns. contg. active ingredients and specified polysiloxanes)				
RN 501947-86-0 HCAPLUS				
CN Propanedioic acid, [[4-[[3-(dihydroxymethylsilyl)-2-propenyl]oxy]phenyl]methylene]-, diethyl ester, homopolymer (9CI) (CA INDEX NAME)				
CM 1				
CRN 208391-14-4				
CMF C18 H24 O7 Si				



L38 ANSWER 2 OF 7 USPATFULL on STN

ACCESSION NUMBER: 2003:13168 USPATFULL

TITLE: Positive working photoresist composition

INVENTOR(S): Mizutani, Kazuyoshi, Shizuoka, JAPAN

Sato, Kenichiro, Shizuoka, JAPAN

Kodama, Kunihiko, Shizuoka, JAPAN

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Kanagawa, JAPAN (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6506535	B1	20030114
APPLICATION INFO.:	US 2000-698221		20001030 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-307317	19991028
	JP 1999-331785	19991122
	JP 1999-338487	19991129
	JP 1999-343714	19991202

DOCUMENT TYPE: Utility

FILE SEGMENT: GRANTED

PRIMARY EXAMINER: Baxter, Janet

ASSISTANT EXAMINER: Clarke, Yvette M.

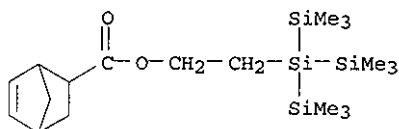
LEGAL REPRESENTATIVE: Sughrue Mion, PLLC  
NUMBER OF CLAIMS: 19  
EXEMPLARY CLAIM: 1,3  
NUMBER OF DRAWINGS: 0 Drawing Figure(s); 0 Drawing Page(s)  
LINE COUNT: 2346  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
IT 337954-60-6P

(acid-decomposable polymers for high-soln. pos. photoresists giving rectangular patterns)

RN 337954-60-6 USPTAFULL  
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]ethyl ester, polymer with 2,5-furandione and methyl 2-propenoate (9CI) (CA INDEX NAME)

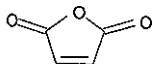
CM 1

CRN 337954-57-1  
CMF C19 H40 O2 Si4



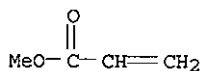
CM 2

CRN 108-31-6  
CMF C4 H2 O3



CM 3

CRN 96-33-3  
CMF C4 H6 O2



L38 ANSWER 3 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 2

ACCESSION NUMBER: 2001:726601 HCAPLUS  
DOCUMENT NUMBER: 135:280511  
TITLE: Positive-working photoresist compositions showing high resolution and high sensitivity and excellent storage stability  
INVENTOR(S): Sato, Kenichiro  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 62 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001272784	A2	20011005	JP 2000-385724	20001219
PRIORITY APPLN. INFO.:			JP 1999-363302	A 19991221
			JP 2000-10773	A 20000119
			JP 2000-10774	A 20000119

OTHER SOURCE(S): MARPAT 135:280511

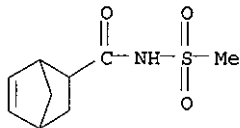
IT 363616-65-3P  
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
(alk.-developing silyl-contg. polymer pos. photoresists having storage stability)

RN 363616-65-3 HCAPLUS  
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethyl-3-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]propyl ester, polymer with 2,5-furandione and N-(methylsulfonyl)bicyclo[2.2.1]hept-5-ene-2-

carboxamide (9CI) (CA INDEX NAME)

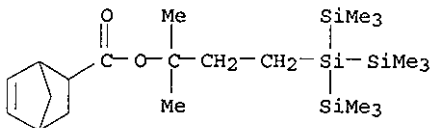
CM 1

CRN 363616-64-2  
CMF C9 H13 N O3 S



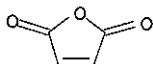
CM 2

CRN 250589-01-6  
CMF C22 H46 O2 Si4



CM 3

CRN 108-31-6  
CMF C4 H2 O3



L38 ANSWER 4 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 3

ACCESSION NUMBER: 2001:423557 HCAPLUS  
DOCUMENT NUMBER: 135:38893  
TITLE: Positive photoresist compositions for manufacture of semiconductor devices  
INVENTOR(S): Sato, Kenichiro; Kodama, Kunihiro; Mizutani, Kazuyoshi  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 66 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 4  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001159812	A2	20010612	JP 1999-343714	19991202
US 6506535	B1	20030114	US 2000-698221	20001030

PRIORITY APPLN. INFO.: JP 1999-307317 A 19991028  
JP 1999-331785 A 19991122  
JP 1999-338487 A 19991129  
JP 1999-343714 A 19991202

OTHER SOURCE(S): MARPAT 135:38893

IT 337954-60-6P

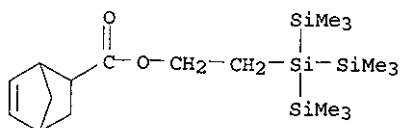
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
(acid-decomposable polymers; improvement of exposure margin in pos. photoresists for manuf. of semiconductor devices)

RN 337954-60-6 HCAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]ethyl ester, polymer with 2,5-furandione and methyl 2-propenoate (9CI) (CA INDEX NAME)

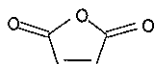
CM 1

CRN 337954-57-1  
CMF C19 H40 O2 Si4



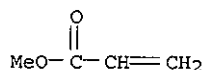
CM 2

CRN 108-31-6  
CMF C4 H2 O3



CM 3

CRN 96-33-3  
CMF C4 H6 O2



L38 ANSWER 5 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 4

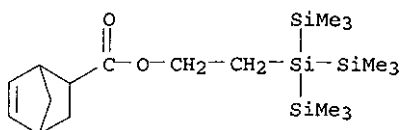
ACCESSION NUMBER: 2001:414682 HCAPLUS  
DOCUMENT NUMBER: 135:26888  
TITLE: Alkali-developable positive-working photoresist composition  
INVENTOR(S): Sato, Kenichiro; Mizutani, Kazuyoshi  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 71 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 4  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001154361	A2	20010608	JP 1999-338487	19991129
US 6506535	B1	20030114	US 2000-698221	20001030
PRIORITY APPLN. INFO.:				
			JP 1999-307317	A 19991028
			JP 1999-331785	A 19991122
			JP 1999-338487	A 19991129
			JP 1999-343714	A 19991202

IT 337954-60-6P  
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
(polymer in alkali-developable pos.-working photoresist compn.)  
RN 337954-60-6 HCAPLUS  
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]ethyl ester, polymer with 2,5-furandione and methyl 2-propenoate (9CI) (CA INDEX NAME)

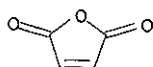
CM 1

CRN 337954-57-1  
CMF C19 H40 O2 Si4



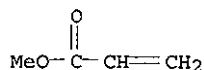
CM 2

CRN 108-31-6  
CMF C4 H2 O3



CM 3

CRN 96-33-3  
CMF C4 H6 O2



L38 ANSWER 6 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 5

ACCESSION NUMBER: 2001:388948 HCAPLUS  
DOCUMENT NUMBER: 135:12122  
TITLE: Positive-working photoresist composition containing sulfonium compound acid generator  
INVENTOR(S): Sato, Kenichiro; Mizutani, Kazuyoshi  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 65 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 4  
PATENT INFORMATION:

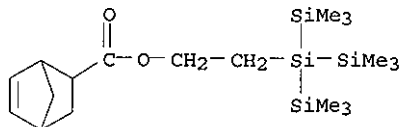
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001147536	A2	20010529	JP 1999-331785	19991122
US 6506535	B1	20030114	US 2000-698221	20001030
PRIORITY APPLN. INFO.:			JP 1999-307317	A 19991028
			JP 1999-331785	A 19991122
			JP 1999-338487	A 19991129
			JP 1999-343714	A 19991202

OTHER SOURCE(S): MARPAT 135:12122

IT 337954-60-6P  
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
(photoresist compn. contg. sulfonium compd. acid generator, acid-decomposable polymer, basic compd. and surfactant)  
RN 337954-60-6 HCAPLUS  
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]ethyl ester, polymer with 2,5-furandione and methyl 2-propenoate (9CI) (CA INDEX NAME)

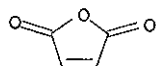
CM 1

CRN 337954-57-1  
CMF C19 H40 O2 Si4



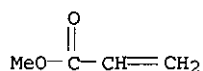
CM 2

CRN 108-31-6  
CMF C4 H2 O3



CM 3

CRN 96-33-3  
CMF C4 H6 O2

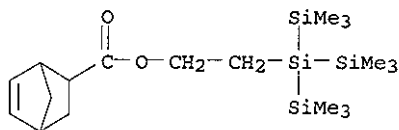


L38 ANSWER 7 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 6  
 ACCESSION NUMBER: 2001:336598 HCAPLUS  
 DOCUMENT NUMBER: 134:346473  
 TITLE: High-resolution positive photoresist compositions  
 INVENTOR(S): Mizutani, Kazuyoshi  
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
 SOURCE: Jpn. Kokai Tokkyo Koho, 60 pp.  
 CODEN: JKXXAF  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 4  
 PATENT INFORMATION:

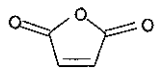
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001125272	A2	20010511	JP 1999-307317	19991028
US 6506535	B1	20030114	US 2000-698221	20001030

PRIORITY APPLN. INFO.:  
 JP 1999-307317 A 19991028  
 JP 1999-331785 A 19991122  
 JP 1999-338487 A 19991129  
 JP 1999-343714 A 19991202

IT 337954-60-6P  
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
 (acid-decomposable polymers for high-soln. pos. photoresists giving rectangular patterns)  
 RN 337954-60-6 HCAPLUS  
 CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]ethyl ester, polymer with 2,5-furandione and methyl 2-propenoate (9CI) (CA INDEX NAME)  
 CM 1  
 CRN 337954-57-1  
 CMF C19 H40 O2 Si4



CM 2  
 CRN 108-31-6  
 CMF C4 H2 O3



CM 3  
 CRN 96-33-3  
 CMF C4 H6 O2

